

FORM PTO-1449 (MODIFIED)

ATTORNEY DOCKET NO.

SERIAL NO.

LIST OF PATENTS AND
PUBLICATIONS
FOR APPLICANTS INFORMATION
DISCLOSURE STATEMENT

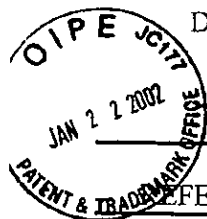
SP00-314

09/943,252

APPLICANT Best et al.

FILING DATE August 30, 2001

GROUP 2872 1731



REFERENCE DESIGNATION

U.S. PATENT DOCUMENTS

Examiner Initial		Document Number	Date	Name	Class	Sub-Class	Filing Date if Approp.
	AA	5,315,629	5/24/94	Jewell et al.	378	34	
SV	AB	6,280,294	8/28/01	Miyamoto	451	34	
SV	AC	6,312,317	11/6/01	Oguma	451	42	
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						
	AJ						
	AK						

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TC 1700

FOREIGN PATENT DOCUMENTS

		Document Number	Date	Country	Class	Sub-Class	Translat Yes
	AL						
	AM						
	AN						
	AO						
	AP						
	AQ						

OTHER ART (Including Author, Title, Date, Pertinent Pages, etc.)

SV	AR		Gianoulakis et al. Proceedings Of the SPIE - The International Society for Optical Engineering (1999), vol. 3676, pt. 1-2, p. 598-605. ABSTRACT ONLY
	AS		
	AT		

EXAMINER:

Sean Vincent

DATE CONSIDERED:

12-27-03

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Information Disclosure Statement-PTO-1449 (Modified)

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Best et al

FILING DATE

8-30-01

GROUP TO

BE ASSIGNED *28A 1731*

REFERENCE DESIGNATION

U.S. PATENT DOCUMENTS

Examiner Initial		Document Number	Date	Name	Class	Sub-Class	Filing Date if Approp.
<i>SV</i>	AA	3,958,052	5/18/76	Galusha et al.			
<i>SV</i>	AB	4,130,437	12/19/78	Mazeau et al.			
<i>SV</i>	AC	4,231,827	11/4/80	Wilson et al.			
<i>SV</i>	AD	4,282,021	8/4/81	Mazeau et al.			
<i>SV</i>	AE	5,750,448	5/12/98	Grabowski et al.			
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FOREIGN PATENT DOCUMENTS

		Document Number	Date	Country	Class	Sub-Class	Translation Yes	No
	AL							
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	AN							
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	AQ							

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99/043,252

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APPLICANT: Best et al.

TC 1700

FILING DATE: August 30, 2001

GROUP: 2872/1731



REFERENCE DESIGNATION

U.S. PATENT DOCUMENTS

Examiner Initial		Document Number	Date	Name	Class	Sub-Class	Filing Date if Approp.
SV	AA	2,239,551	4/22/41	Dalton et al.	49	79	
SV	AB	2,272,342	2/10/42	Hyde	49	78.1	
SV	AC	4,002,512	1/11/77	Lim	148	187	
SV	AD	4,231,657	11/4/80	Iwamatsu	355	71	
SV	AE	4,344,816	8/17/82	Craighead et al.	156	643	
SV	AF	4,411,013	10/18/83	Takasu et al.	378	34	
SV	AG	4,776,696	10/11/88	Hettrick et al.	356	328	
SV	AH	4,911,513	3/27/90	Valette	350	96.12	
SV	AI	5,003,567	3/26/91	Hawryluk et al.	378	34	
SV	AJ	5,016,265	5/14/91	Hoover	378	43	
SV	AK	5,043,002	8/27/91	Dobbins et al.	65	3.12	
SV	AL	5,051,326	9/24/91	Celler et al.	430	5	
SV	AM	5,146,482	9/8/92	Hoover	378	43	
SV	AN	5,146,518	9/8/92	Mak et al.	385	41	
SV	AO	5,152,819	10/6/92	Blackwell et al.	65	3.12	
SV	AP	5,154,744	10/13/92	Blackwell et al.	65	3.12	
SV	AQ	5,165,954	11/24/92	Parker et al.	427	526	
SV	AR	5,173,930	12/22/92	Hoover	378	85	
SV	AS	5,220,590	6/15/93	Bruning et al.	378	34	
SV	AT	5,304,437	4/19/94	Tennant	430	5	
SV	AU	5,315,629	5/24/94	Jewell et al.	378	34	
SV	AV	5,328,784	7/12/94	Fukuda	430	5	
SV	AW	5,332,702	7/26/94	Sempolinski et al.	501	106	
SV	AX	5,353,322	10/4/94	Bruning et al.	378	34	
SV	AY	5,356,662	10/18/94	Early et al.	427	140	
SV	AZ	5,389,445	2/14/95	Makowiecki et al.	428	457	

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GROUP: 2872 / 731

REFERENCE DESIGNATION

U.S. PATENT DOCUMENTS

Examiner	Document Number	Date	Name	Class	Sub-Class	Filing Date if Approp.
SV	AA1	5,395,413	3/7/95	Sempolinski et al.	65	414
SV	AB1	5,395,738	3/7/95	Brandes et al.	430	296
SV	AC1	5,510,230	4/23/96	Tennant et al.	430	325
SV	AD1	5,521,031	5/28/96	Tennant et al.	430	5
SV	AE1	5,553,110	9/3/96	Sentoku et al.	117	35
SV	AF1	5,565,030	10/15/96	Kado et al.	117	89
SV	AG1	5,605,490	2/25/97	Laffey et al.	451	36
SV	AH1	5,698,113	12/16/97	Baker et al.	216	72
SV	AI1	5,637,962	6/10/97	Prono et al.	315	111.21
SV	AJ1	5,737,137	4/7/98	Cohen et al.	359	859
SV	AK1	5,815,310	9/29/98	Williamson	359	365
SV	AL1	5,868,605	2/9/99	Cesna	451	41
SV	AM1	5,880,891	3/9/99	Furter	359	651
SV	AN1	5,970,751	10/26/99	Maxon et al.	65	414
SV	AO1	5,989,776	11/23/99	Felter et al.	430	270.1
SV	AP1	6,013,399	1/11/00	Nguyen	430	5
SV	AQ1	6,048,652	4/11/00	Nguyen et al.	430	5
SV	AR1	6,118,577	9/12/00	Sweatt et al.	359	351
SV	AS1	2001/0028462	10/11/01	Ichihara et al.	356	512

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	Document Number	Date	Country	Class	Sub-Class	Translation Yes No
SV	AA	WO 87/06028	10/8/87	PCT	G03F	1/00 X
SV	AB	98/34234	8/6/98	PCT	G21G	4/00 X
SV	AC	0 055 077	6/30/82	EPO	G03	7/20 X
SV	AD	0 252 734	1/13/88	EPO	G03F	7/20 X
SV	AE	0 279 670	8/24/88	EPO	G03F	1/00 X
SV	AF	0 569 123	11/10/93	EPO	G03F	1/14 X
SV	AG	0 708 367	4/24/96	EPO	G03F	1/00 X
SV	AH	0 710 890	5/8/96	EPO	G03F	7/20 X
SV	AI	0 779 528	6/18/97	EPO	G02B	17/08 X
SV	AJ	0 809 125	11/26/97	EPO	G02B	6/38 X
SV	AK	0 903 605	3/24/99	EPO	G02B	13/14 X
SV	AL	60-173551	9/6/85	Japan (Abstract only)	G03C	005/08 X
SV	AM	63-142302	6/14/88	Japan (Abstract only)	G02B	001/10 X
SV	AN	63-142301	6/14/88	Japan (Abstract only)	G02B	001/10 X
SV	AO	WO 01/07967	2/1/01	PCT	G03C	5/00 X
SV	AP	WO 01/08163	2/1/01	PCT	C23	14/02 X
SV	AQ	WO 01/75522	10/11/01	PCT	G03F	1/14 X

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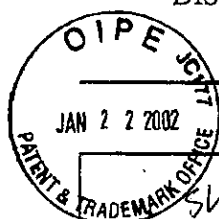
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SV	AA	✓	Tanya E. Jewell, Four-Mirror Ring-Field System for EUV Projection Lithography, 1994, pages 98-102.
SV	AB	✓	High Purity Quartz Glass Products, 5/17/99, http://www.toshiba-ceramics.com/quartz.html , pages 1-2.
SV	AC	✓	Shin-Etsu Chemical Homepage, Semiconductor Materials Division, 5/17/99, http://www.shinetsu.co.jp/english/profile/division/sem-div/sem-div.html , pages 1-2.
SV	AD	✓	Isimoto Co., Ltd., Products for Optics, 5/17/99, http://www.isimoto.ocm/isimoto/english/variation3.html , pages 1-2.
SV	AE	✓	Isimoto Co., Ltd., Product Information, 5/17/99, http://www.isimoto.ocm/isimoto/english/procuct_info.html , pages 1-4.
SV	AF	✓	Isimoto Co., Ltd., Purity and Chemical Reactivity, 5/17/99, http://www.isimoto.ocm/isimoto/english/feature1.html , pages 1-3.
SV	AG	✓	The Optics Mall - Equipment/Supplies, Universal Photonics, Inc., 7/7/99, page 1.
SV	AH	✓	Rodel Authored Papers: A Study of the Variation of Physical Properties in Random Lots of Urethane Polishing Pads for CMP, 7/7/99, http://www.rodel.com/publications/paper1.asp , pages 1-4.
SV	AI	✓	Rodel Publications Content, Rodel Authored Papers, 7/7/99, http://www.rodel.com/publications/content.asp , pages 1-2.
SV	AJ	✓	Rodel Publications, 7/7/99, http://www.rodel.com/publications/default.asp , page 1.
SV	AK	✓	Cab-O-Sil Web Site, 7/7/99, http://www.cabot-corp.com/cabosil , pages 1-3.
SV	AL	✓	Optics and Photonics News, August 1999, Vol. 10, No. 8, August 1999, pages 34-38.
SV	AM	✓	O.V. Mazurin, V. K. Leko and L.A. Komarova, Journal of Non-Crystalline Solids 18 (1975) 1-9, Crystallization of Silica and Titanium Oxide-Silica Corning Glasses (Codes 7940 and 7971), pages 1-9.
SV	AN	✓	S. T. Gulati and H.E. Hagy, Journal of the American Ceramic Society, Vol. 61, No. 5-6 May-June, 1978, Theory of the Narrow Sandwich Seal, pages 260-263.
	AO	✓	George H. Beall, Industrial Applications of Silica, pages 470-505.
SV	AP	✓	Extreme Ultraviolet Lithography, A White Paper Prepared by: Charles Gwyn, et al. EUV LLC, Livermore, Ca., November 1999, pp.96-141

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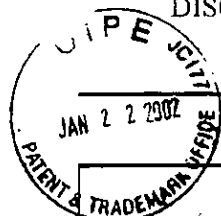
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	APPLICANT Best et al.	
	FILING DATE: August 30, 2001	GROUP: 2872 / 73 /



OTHER ART (Including Author, Title, Date, Pertinent Pages, etc.)

SV	AQ	/	H. E. Hagy and W. D. Shirkey, Determining absolute thermal expansion of titanica-silica glasses: a refined ultrasonic method, September 1975, Vol. 14, No. 9, Applied Optics, pages 2099-2103.
SV	AR	/	S. F. Jacobs et al., Surface figure changes due to thermal cycling hysteresis, Applied Optics, Vol. 26, No. 20, October 15, 1987, pages 4438-4442
SV	AS	/	C.W. Gwyn, R. Stulen, D. Sweeney and D. Attwood, Extreme Ultraviolet Lithography, pages 1-9 and 1-6.
SV	AT	/	Richard H. Stulen and Donald W. Sweeney, Extreme Ultraviolet Lithography, IEEE Journal of Quantum Electronics, Vol. 35, No. 5, May 1999, pages 694-699
	AU	/	William M. Tong, John S. Taylor, Stephen P. Vernon, Substrates Requirements For Extreme Ultraviolet Lithography, Lawrence Livermore National Laboratory.
SV	AV	X	EUV Lithography NGL Technology Review, June 9, 1999.
SV	AX	/	P.C. Schultz et al., Ultra-Low-Expansion Glasses & Their Structure in the SiO ₂ and TiO ₂ System, Papers presented to the Third International Conf. on the Physics of Non-crystalline Solids, Sheffield University September, 1970. 453-461.

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